



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 9635**  
Satoshi MAEMORI et al. : Attorney Docket No. 2001\_1300A  
Serial No. 09/955,111 : Group Art Unit 1752  
Filed September 19, 2001 : Examiner Sin J. Lee

POSITIVE-WORKING PHOTORESIST  
COMPOSITION AND PHOTSENSITIVE  
MATERIAL USING SAME

**Mail Stop: AF**

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**RESPONSE TO FINAL REJECTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Final Rejection dated September 7, 2005, the period for response having been extended for one month by the attached petition, please amend the present application as follows:

Please  
Enter  
SJL  
1-4-06